

REQUEST FOR ACCESS TO AN APPLICATION UNDER 37 CFR 1.14(e)

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In re Application of

Bergman et alApplication Number
09-061318Filed
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Art Unit

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 (A) referred to in:United States Patent Application Publication No. 6,273,108, page _____, line _____.

United States Patent Number _____, column _____, line _____, or

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 (B) referred to in an application that is open to public inspection as set forth in 37 CFR 1.11(b) or

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United States Patent
Bergman et al.

(10) Patent No.: US 6,273,108 B1
(45) Date of Patent: Aug. 14, 2001

- (54) APPARATUS AND METHOD FOR PROCESSING THE SURFACE OF A WORKPIECE WITH OZONE
- (75) Inventors: Eric J. Bergman; Mignon P. Hess, both of Kalispell, MT (US)
- (73) Assignee: Semitool, Inc., Kalispell, MT (US)
- (*) Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 0 days.

(21) Appl. No.: 09/677,929

(22) Filed: Oct. 3, 2000

Related U.S. Application Data

- (60) Division of application No. 09/061,318, filed on Apr. 16, 1998, which is a continuation-in-part of application No. 08/853,649, filed on May 9, 1997.
- (51) Int. Cl. 7 B08B 3/02
- (52) U.S. Cl. 134/102.1; 134/95.3; 134/105; 134/902; 134/111; 134/103.1
- (58) Field of Search 134/94.1, 95.1, 134/95.2, 95.3, 99.2, 102.1, 103.1, 105, 107, 108, 111, 102

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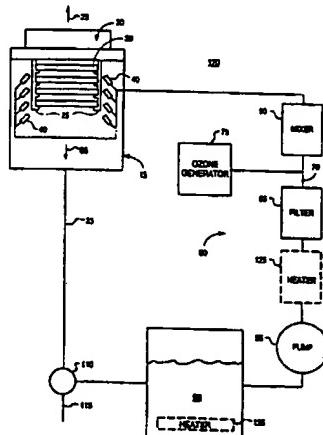
(List continued on next page.)

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(57) ABSTRACT

An apparatus for supplying a mixture of a treatment liquid and ozone for treatment of a surface of a workpiece, and a corresponding method are set forth. The preferred embodiment of the apparatus comprises a liquid supply line that is used to provide fluid communication between a reservoir containing the treatment liquid and a treatment chamber housing the workpiece. A heater is disposed to heat the workpiece, either directly or indirectly. Preferably, the workpiece is heated by heating the treatment liquid that is supplied to the workpiece. One or more nozzles accept the treatment liquid from the liquid supply line and spray it onto the surface of the workpiece while an ozone generator provides ozone into an environment containing the workpiece.

21 Claims, 6 Drawing Sheets



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